

Plasma generator RPG-250



RPG at work

High efficiency plasma generator based on high frequency induction discharge (transformer coupled TCP plasma).

Plasma generator is a universal technological device for wide application of ion-plasma processing processes, meets all the requirements for industrial production.

RPG-250 allows to ensure high uniformity of processing, up to 2% at a diameter of 200 mm (in a reactor of special design).

The main element of the generator is a flat coil through which an industrial frequency current (13.56 MHz) is passed. The generators are made in an aluminum case, equipped with a coaxial input.

The working surface is protected by sapphire and a removable protective quartz glass screen, which makes it easy to clean.

RPG-128 is an electrodeless low-temperature high-density plasma generator designed to be installed inside the technological volume of a vacuum chamber. The device can be used for a wide range of technological processes:

- high temperature annealing
- ionic cleaning and assistance
- ionic surface modification (oxidation, reduction, nitriding, carbidization, etc.)
- plasma-assisted vapor deposition
- evaporation, including with additional ionization of vapors
- ionic and plasma-chemical etching
- spraying of various materials in the plasma of inert or chemically active gases

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"Standard set"



SURA

The ion-plasma system consists of:
RPG-128 (or RPG-250) - radio frequency plasma generator
Matching device - SURA
RF generator

The RF generator is placed in a rack (for versions complete with a vacuum unit).

Technological devices (SURA and RPG) are placed motionless in the chamber.



RF generator



RPG - radio frequency plasma generator is protected by patents of the Russian Federation and others.

Patents:
RF RU 2503 079 C1
Japan 6292484
USA US9704691

